



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In Re Application of:
Ratnam SOORIYAKUMARAN et al.

Confirmation No.: 7983

Serial No.: 10/079,289

Group Art Unit: 1752

Filing Date: February 19, 2002

Examiner: Yvette C. THORNTON

Title: FLUORINATED SILSESQUIOXANE POLYMERS
AND USE THEREOF IN LITHOGRAPHIC
PHOTORESIST COMPOSITIONS (as amended
herein)

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THIRD PRELIMINARY AMENDMENT AND
RESPONSE TO REQUIREMENT FOR RESTRICTION

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

This is in response to the Office Action mailed September 23, 2003 concerning the patent application referenced above. The Action sets forth a requirement for restriction and is not an Action on the merits. As such, a one-month shortened statutory period has been set for response. Applicants' response is set forth herein, along with amendments to the claims.

A Supplemental Information Disclosure Statement is submitted herewith, along with copies of the cited references, U.S. Patent Nos. 6,531,260 to Iwasawa et al. and 6,623,909 to Hatakeyama et al.

An Amendment to the Title is set forth on page 2 of this document.

Amendments to the Claims are reflected in the listing of the claims which begins on page 3 of this document.

Remarks begin on page 14 of this document.

AMENDMENT TO THE TITLE

On page 1 of the application, at lines 1-2, on page 71 of the application, at lines 1-2, and wherever the title appears in the application documents, please change the title to read

**--FLUORINATED SILSESQUOXANE POLYMERS AND
USE THEREOF IN LITHOGRAPHIC PHOTORESIST COMPOSITIONS--.**